

The organometallic interest of this sub-volume derives mainly from the large number of radicals with organometallic substituents, and the use of organometallic compounds to produce the radicals. Approximately 15% of the radicals listed in this volume have an organometallic substituent. Silicon, phosphorus, germanium and tin substituents are the most numerous, with smaller numbers of substituents containing Se, B, Pb, Ag, Au, Al, Cu, and Cr. A large number of examples involve the addition of metal-centred radicals to C=X multiple bonds of various types. A significant number of entries demonstrate the use of organometallic reagents to prepare radicals without organometallic substituents; for example, photolysis of organometallic compounds to cleave carbon-metal bonds, and the use of tin-centred radicals to remove halogen atoms from organic halides.

The production is superb, and the reviewer noticed only one typographical mistake. All organometallic chemists interested in free-radical chemistry will wish to have access to this series of sub-volumes.

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**Richard A. Jackson**

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*Inorganic Reactions and Methods. Volume 11. The Formation of Bonds to Elements of group IVB (C, Si, Ge, Sn, Pb) (Part 3).* Editor: J.J. Zuckermann, VCH Weinheim, etc., 1988. xxiv + 594 pages. DM 284. ISBN 3-527-26269-5

The most striking feature of the copy of this volume sent to me for review is that by a gross error on the part of the publishers, which has no doubt caused them considerable embarrassment, it is described in prominent gold lettering on the outside front cover as "*Volume 11, The Formation of Bonds to Hydrogen (Part 2)*". Such is the complexity of the organization of this series of volumes that it took me some time to convince myself that this was, indeed, just a simple error, and that the actual title should have been that given in the heading of this review.

The book deals with the methods of forming bonds between elements of group IVB (C, Si, Ge, Sn, and Pb) and elements of (i) group IA (Li, Na, K, Rb, Cs, Fr); (ii) group IB (Cu, Ag, Au), and (iii) group IIB (Zn, Cd, Hg). Given the space limitations the accounts are all that could be expected, and will provide very useful concise introductions to the topics for newcomers to the various fields. The only obvious weakness is that the organization of the material inhibits comparison of the advantages and limitations of the various methods, so that someone wanting to find out which is the best method of making a particular type of compound will have to examine the cited literature in detail.

Aspects of presentation can be criticized. A minor defect is that in places there is excessive emphasis on safety aspects, (though this is less marked than in other volumes in the series,) with little consistency from section to section. For example, in the first 31 pages on the formation of organolithium compounds the warning "Organolithium solutions are pyrophoric and should be handled with care" is printed in bold type six times, and then, with a change of author, no such warning appears again in the remaining 117 pages on the subject. A much more serious criticism is that, in my view, there is no justification for devoting 228 out of the total

of 594 pages to indexes. Some 153 pages are devoted to a Compound Index (a formula index; with much blank space on the pages,) in which, for example, the compound  $C_{34}H_{40}Ag_4Au_2F_6N_4O_6S_2$  appears also in its seven permutations,  $H_{40}Ag_4Au_2F_6N_4O_6S_2C_{34}$ , etc. Since the various accounts are illustrative rather than comprehensive, the chances are not high that the particular compound one wishes to make will appear, and in any case it is better to read the complete account of the available methods to see whether any closely related compound is mentioned. I also cannot envisage a situation in which, with a volume of this type, I would want to use the Author Index (which takes up 56 pages, and is extravagantly set out) – except, of course, to see if any of my own papers are mentioned! (Doing this, I found, that one of them is attributed to a C. Eaborn). In my judgement, it would have been better to omit both the Author Index and Formula Index, and perhaps expand the Subject Index.

As part of the complete series this volume will be a valuable source of information, and should be in all chemical reference libraries.

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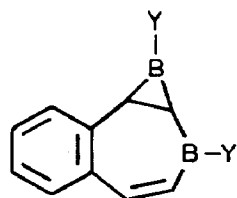
**Colin Eaborn**

## Erratum

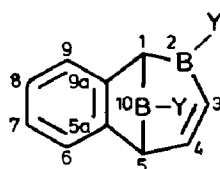
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**Zur Borylierung von Benzol und Naphthalin durch Dehalogenierungsprodukte von Dichlor(diisopropylamino)boran;** by A. Meller, D. Bromm, W. Maringele, D. Böhler und G. Elter (*J. Organomet. Chem.*, 347 (1988) 11–16).

Page 14, Formulae IIIa and IIIb should read:



(IIIa)



(IIIb)